

Search Notes

Application No.

10/775,683

Examiner

D. Rutledge

Applicant(s)

MATSUMOTO ET AL.

Art Unit

2851

SEARCHED

Class	Subclass	Date	Examiner
355	52,53,55, 67	9/18/2004	DR
359	672,673	9/18/2004	DR
359	675	9/18/2004	DR

INTERFERENCE SEARCHED

Class	Subclass	Date	Examiner
355	52,53,55	9/18/2004	DR
355	67	9/18/2004	DR
359	672, 673	9/18/2004	DR
359 675		9/18/2004	DR

**SEARCH NOTES
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
mask or reticle, board or circuit adj board or printed circuit; magnification, correct\$3 or adjust\$4 or modification modify\$3	9/18/2004	DR
first or second, lens\$2, first or plano adj convex or plano adj concave, optical adj power,	9/18/2004	DR
wafer or substrate, photomask, telecentric	9/18/2004	DR